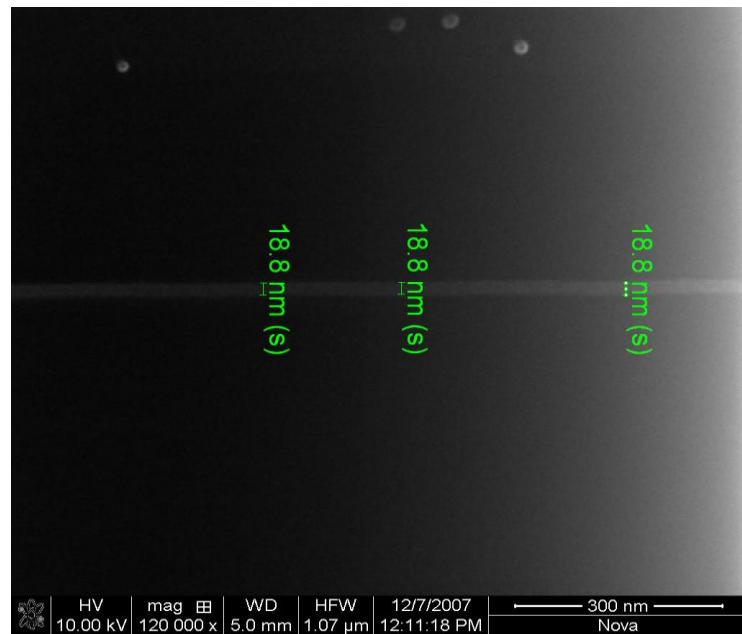


FIB-電子束離子束雙束系統技術資料

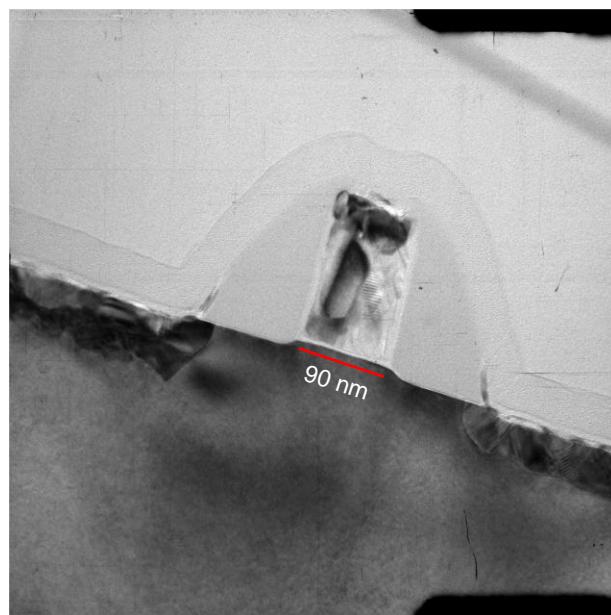
陳俊淇

國家奈米元件實驗室微影光罩組

19nm Pt line



TEM preparation result (device structure) thickness <100 nm



HR TEM result (gate stack): No amorphous damage

